

RESIN FOR PHOTOFORMATION METHOD**Publication number:** JP2001048932 (A)**Publication date:** 2001-02-20**Inventor(s):** MURAKAMI TAMOTSU**Applicant(s):** SENTAN KAGAKU GIJUTSU INCUBATI**Classification:**

- international: *B29C67/00; C08F2/54; C08F20/10; C08F299/00; C08L101/00; C08L101/16; B29C67/00; C08F2/46; C08F20/00; C08F299/00; C08L101/00; (IPC1-7): C08F20/10; B29C67/00; C08F2/54; C08F299/00; C08L101/16*

- European:**Application number:** JP19990225683 19990809**Priority number(s):** JP19990225683 19990809**Abstract of JP 2001048932 (A)**

PROBLEM TO BE SOLVED: To provide a resin which is used for photoformation methods and enables the formation of three-dimensional formed products having high surface accuracy by simple means. **SOLUTION:** This resin for photoformation methods contains an X-ray curable component which can sensitively be cured by the irradiation of X-rays having a stronger substance-penetrating force than that of UV light. Since the resin composition can be photocured using the X-rays, operation labors can be reduced, when a three-dimensional formed product having a large width in the depth direction is formed. Since the joined portions of cured resin layers can further be decreased, the unevenness of the surfaces of the formed product can be reduced.

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